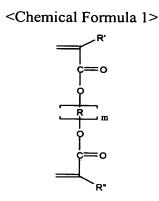


## CROSS-LINKING MONOMERS FOR PHOTORESIST, AND PROCESS FOR PREPARING PHOTORESIST POLYMERS USING THE SAME

## ABSTRACT OF THE DISCLOSURE

The present invention discloses a cross-linking monomer represented by the following Chemical Formula 1, a process for preparing a photoresist polymer using the same, and said photoresist polymer:



wherein, R' and R" individually represent hydrogen or methyl; m represents a number of 1 to 10; and R is selected from the group consisting of straight or branched  $C_{1-10}$  alkyl, straight or branched  $C_{1-10}$  ester, straight or branched  $C_{1-10}$  ketone, straight or branched  $C_{1-10}$  carboxylic acid, straight or branched  $C_{1-10}$  acetal, straight or branched  $C_{1-10}$  alkyl including at least one hydroxyl group, straight or branched  $C_{1-10}$  ester including at least one hydroxyl group, straight or branched  $C_{1-10}$  ketone including at least one hydroxyl group, straight or branched  $C_{1-10}$  acetal including at least one hydroxyl group, and straight or branched  $C_{1-10}$  acetal including at least one hydroxyl group.

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